



6/A  
12/15/01  
Harrison  
Patent

Attorney's Docket No. 015290-440

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Rajinder Dhindsa et al.

Application No.: 09/689,845

Filed: October 13, 2000

For: STEPPED UPPER ELECTRODE  
FOR PLASMA PROCESSING  
UNIFORMITY

)  
)  
) Group Art Unit: 2813  
)  
) Examiner: K. Christianson  
)  
)  
)  
)  
)  
)

RECEIVED  
DEC 21 2001  
TECHNOLOGY CENTER 2800

AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Official Action dated September 26, 2001, please amend the application as follows.

IN THE CLAIMS:

Please replace Claim 19 as follows:

19. (Amended) A plasma chamber for use in manufacturing a semiconductor device, said plasma chamber including a top electrode and a bottom electrode having opposed surfaces facing each other and spaced apart from one another to define a gap therebetween, the bottom electrode comprising a substrate support, and the opposed surface of the top electrode being an exposed surface comprising a central portion and a step projecting from a peripheral portion thereof and extending at least partially around the central portion, the step controlling a localized density of the plasma formed adjacent the exposed surface of the top electrode.